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## INFORMATION DISCLOSURE STATEMENT BY APPLICANT

(use as many sheets as necessary)

Sheet 2 of 2

### Complete if Known

Application Number	
Filing Date	HEREWITH
First Named Inventor	Kiyotaru HASEGAWA, et al.
Group Art Unit	1752
Examiner Name	Y. Thornton
Attorney Docket Number	KOJIM-428

### OTHER PRIOR ART -- NON PATENT LITERATURE DOCUMENTS

Examiner Initials *	Cite No. <sup>1</sup>	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published.	T <sup>2</sup>
yct	✓	W. Brunsvold, et al., "Evaluation of a Deep UV Bilayer Resist for Sub-Half Micron Lithography", pages 377-387	
yct	✓	Carl R. Kessel, et al., "Novel Silicon-Containing Resists for EUV and 193 nm Lithography", March 1999, pages 214-220	
yct	✓	Qinghuang Lin, et al., "A High Resolution 248 nm Bilayer Resist", March 1999, pages 241-250	
yct	✓	Larry D. Boardman, et al., "Chemical Aspects of Silicon-Containing Bilayer Resists", March 1999, pages 562-572	
yct	✓	Jin-Beak Kim, et al., "Chemically amplified resist based on the methacrylate polymer with 2-trimethylsilyl-2-propyl ester protecting group", March 1999, page 420-428	
yct		SPIE vol. 1925 (1993) p. 377-387	
yct		SPIE vol. 3678 (1999) p. 214-220, p. 241-250, p. 562-572, p. 420-428	

Examiner  
Signature

*Yvette C. Johnston*

Date  
Considered

4-30-03

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